

Erratum

The inactivation mechanism of chemical disinfection against SARS-CoV-2: The MD and DFT perspectives(RSC Advances (2020) 10 (40480–40488) DOI: 10.1039/D0RA06730J)

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Correction: The inactivation mechanism of chemical disinfection against SARS-CoV-2: from MD and DFT perspectives

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Correction for 'The inactivation mechanism of chemical disinfection against SARS-CoV-2: from MD and DFT perspectives' by Chunjian Tan *et al.*, *RSC Adv.*, 2020, **10**, 40480–40488, DOI: 10.1039/D0RA06730J.

The authors regret that one of the affiliations (affiliation f) was incorrectly omitted in the original manuscript. The corrected list of affiliations is as shown below.

The Royal Society of Chemistry apologises for these errors and any consequent inconvenience to authors and readers.

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